

Amendments to the Abstract

Please replace the Abstract on page 10 of the application with the following paragraph.

A method of fabricating a photomask includes transferring a is disclosed. ~~The method facilitates accurate measurement of the photomask critical dimension, without requiring the removal of the pellicle. A first pattern is transferred on~~ onto a substrate in a first area, and transferring at least one test pattern ~~is transferred on~~ onto the substrate outside of the first area. A pellicle is attached to the substrate, wherein and the pellicle covers the first area, but does not cover the at least one test pattern.